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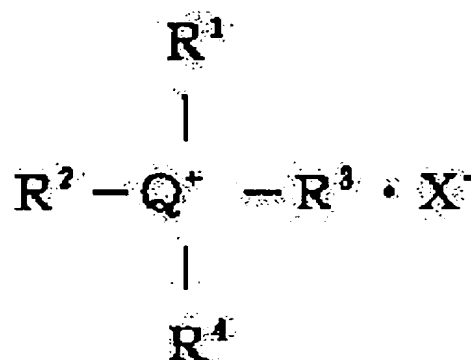
(54) ANTISTATIC AGENT HAVING EXCELLENT HEAT RESISTANCE USED FOR RESIN, AND ANTISTATIC RESIN COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain an antistatic agent not undergoing heat decomposition during thermal molding or heating by using a compound having a counter anion being a super strong acid and one cationic group bonded to a nonionic molecular chain.

SOLUTION: This compound is represented by the formula (wherein Q is N or P; R<sup>1</sup> to R<sup>4</sup> are each contains a nonionic molecular chain in the group (provided that two of them may be combined with each other to form a ring); and X is an anion of a super acid).

The counter anion is desirably a super strong acid having a Hammett's acidity function (-H<sub>0</sub>) of 12 or above and is exemplified by a super strong acid (tetrafluoroboric acid or hexafluorophosphoric acid)



derived from a combination of a proton acid with a Lewis acid or trifluoromethanesulfonic acid. The amount of the antistatic agent added to a resin is usually 0.1/99.9 to 10/90 in terms of an antistatic agent/thermoplastic resin weight ratio.

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